



<b>Session Title:</b>	<b>[TA3] Advanced Atomic Scale Thin Films V</b>
<b>Session Date:</b>	<b>November 21 (Tue.), 2023</b>
<b>Session Time:</b>	<b>14:25-16:15</b>
<b>Session Room:</b>	<b>Room A (Capri Room, 2F)</b>
<b>Session Chair:</b>	<b>Dr. Hanwool Yeon (GIST, Korea)</b>

**[TA3-1] [Invited] 14:25-14:55**

**Molybdenum Precursors and Deposition Mechanisms**

Seán T. Barry (Carleton Univ., Canada)

**[TA3-2] [Invited] 14:55-15:15**

**Atomistic Modeling of Electronics and Thermodynamics of Defects on Titania Surfaces under Environmental Condition**

Ngoc Linh Nguyen (Phenikaa Univ., Vietnam)

**[TA3-3] [Invited] 15:15-15:35**

**Atomic Layer Deposition of Silicon Oxide Films Using Tris(dimethylamino)silane and Ozone**

Okhyeon Kim, Yoonho Choi, Changgyu Kim, Hye-Lee Kim, and Won-Jun Lee (Sejong Univ., Korea)

**[TA3-4] 15:35-15:55**

**Computational Fluid Dynamics Analysis of Cyclone-Type Vaporizer for Mass Delivery of Atomic Layer Deposition Precursors**

Seung-Ho Seo (GO Element Co., Ltd., Korea), Donggeon Shin, Cha-Hee Kim (Sejong Univ., Korea), Yeongjong Lee, Keun-Tae Jeong, Deahyun Kim (GO Element Co. Ltd., Korea), and Won-Jun Lee (Sejong Univ., Korea)

**[TA3-5] 15:55-16:15**

**Novel Liquid Precursors of Group IV/V Transition Metals for High Temperature ALD Process**

Sunyoung Baik, Woongjin Choi, Taeyoung Lee, Shinbeom Kim, Sungjun Ji, Juhwan Jeong, Jaemin Kim, Myungil Kim, Hana Kim, Hyunju Jung, and Kyuho Cho (EGTM, Korea)